



# 6/6th to 11/11th  
2/4/02  
PATENTS

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Takeo MATSUKI et al.

Serial No. 09/764,880

GROUP 2818

Filed January 23, 2001

Examiner T. Nguyen

SEMICONDUCTOR DEVICE STRUCTURE  
AND METHOD FOR MANUFACTURING  
THE SAME

RECEIVED  
FEB - 4, 2002  
TC 2800 MAIL ROOM

**REQUEST TO MAKE DRAWING CORRECTION**

Commissioner for Patents  
Washington, D.C. 20231

Sir:

Permission is respectfully requested to amend  
Figures 2B, 4, 5A, 5B, 5C and 6 of the drawings in the  
above-identified application as shown in red on the  
accompanying prints.

Respectfully submitted,

YOUNG & THOMPSON

By

*Liam McDowell*

Liam McDowell  
Attorney for Applicants  
Registration No. 44,231  
745 South 23<sup>rd</sup> Street  
Arlington, VA 22202  
Telephone: 703-521-2297

January 22, 2002

Fig. 2A

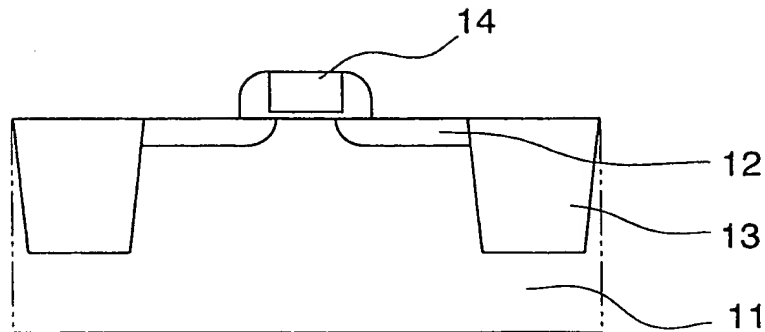


Fig. 2B

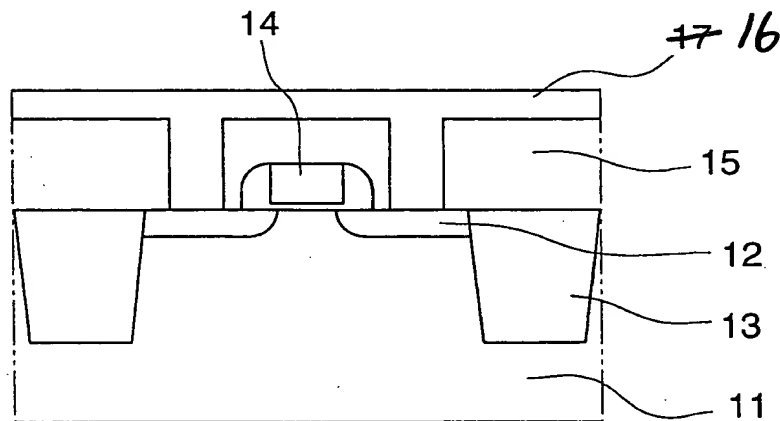


Fig. 2C

SURFACE LEVEL OF  
FIRST INSULATING FILM  
AFTER IT IS ETCHED

SURFACE LEVEL OF FIRST  
INTERLAYER INSULATING FILM AFTER  
POLYSILICON IS ETCHED BACK

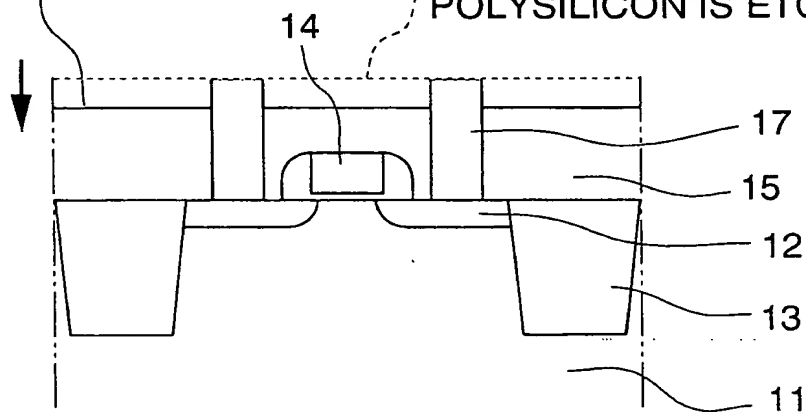


Fig. 4

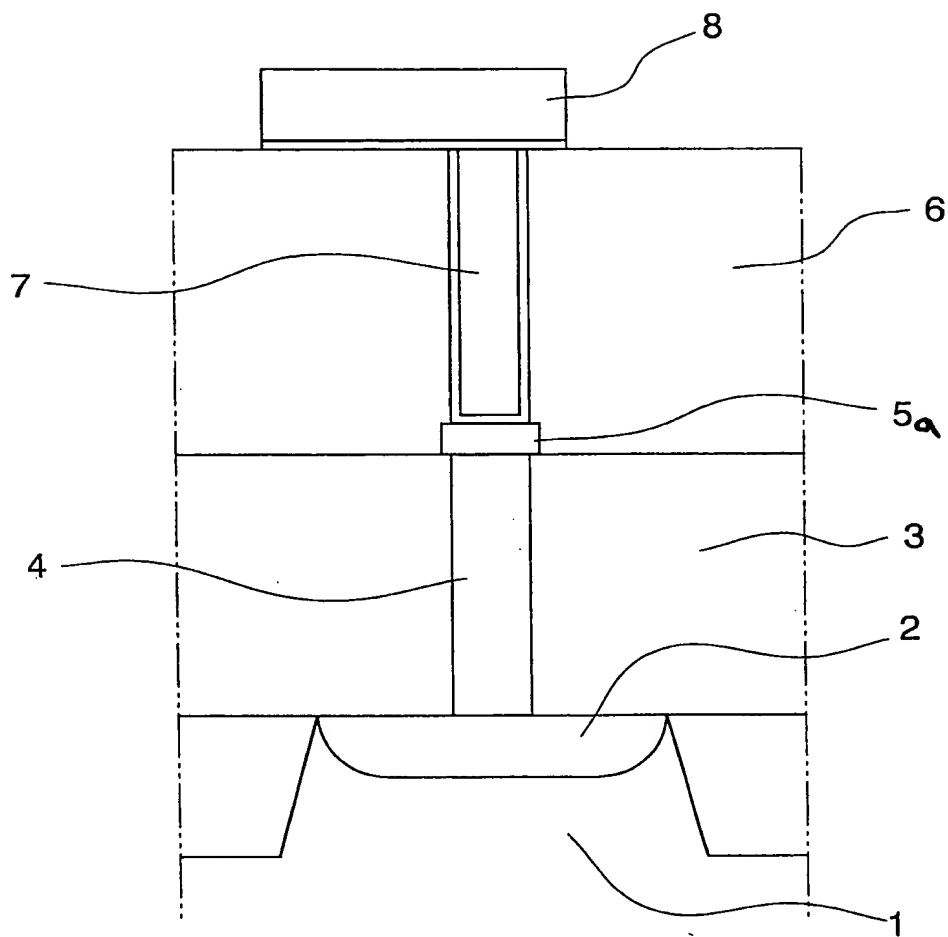


Fig. 5A (Prior Art)

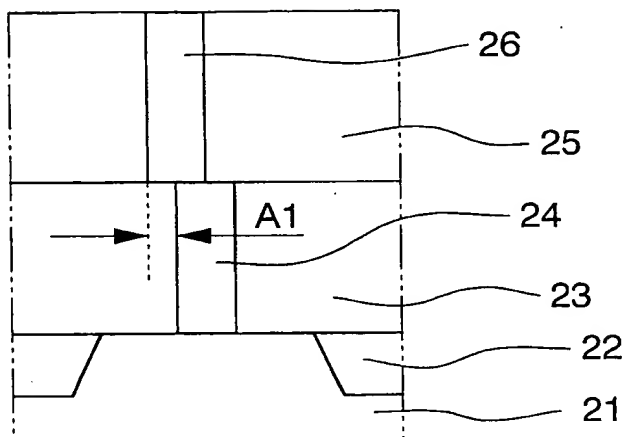


Fig. 5B (PRIOR ART)

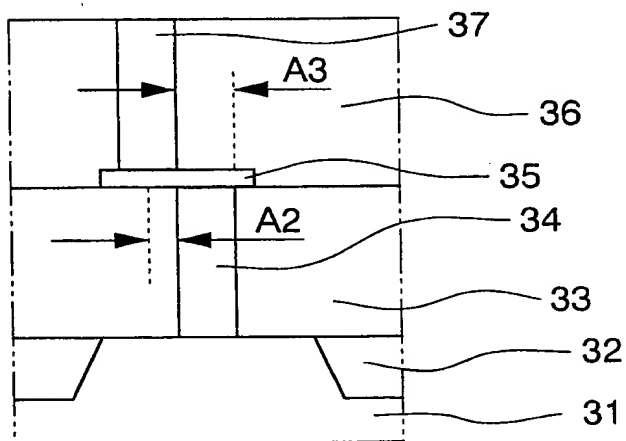


Fig. 5C (PRIOR ART)

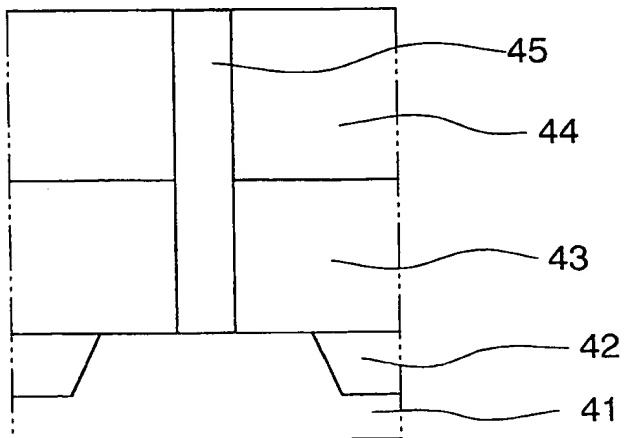


Fig. 6 (PRIOR ART)

